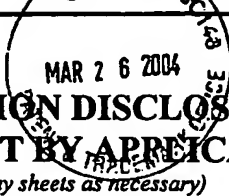
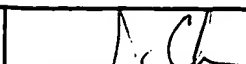


Substitute for form 1449A/PTO			<div style="text-align: center;">  </div>		
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> (use as many sheets as necessary)			<b>Complete if Known</b>		
			Application Number	10/729,452	
			Filing Date	December 4, 2003	
			First Named Inventor	Robert David ALLEN et al.	
			Art Unit	1756	
Examiner Name	Unassigned				
Attorney Docket Number	ARC920030104US1				
Sheet	1	of	1		

U.S. PATENT DOCUMENTS							
Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
JDC	AA	5,391,587	2/21/95	Wu	522	40	
	AB	5,665,527	9/9/97	Allen et al.	430	225	
	AC	5,919,597	7/6/99	Sinta et al.	430	270.1	
	AD	6,037,097	3/14/00	Bucchignano et al.	430	270-1	
	AE	6,043,003	3/28/00	Bucchignano et al.	430	226	
	AF	6,265,135	7/24/01	Kodama et al.	430	280.1	
	AG	Serial No. 10/716,785	Filed 11/19/03	Angelopoulos et al.	430	270-1	
	AH	Serial No. 10/729,169	Filed 12/4/03	Robert David Allen et al.	430	266	

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Examiner Initials*	Cite No.	Foreign Patent Document No.	Publication Date	Country	Class	Subclass	T
JDC	AI	WO 01/86352	11/15/01	PCT			
	AJ	WO 02/079287	10/10/02	PCT			
	AK	WO 03/040827	5/15/03	PCT			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS							
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					T
JDC	AL	BAE et al. (2003), "Rejuvenation of 248 nm Resist Backbones for 157 nm Lithography," <i>Journal of Photopolymer Science and Technology</i> 14(4):613-620.					
	AM	ITO et al. (2001), "Polymer Design for 157 nm Chemically Amplified Resists," <i>Advances In Resist Technology And Processing XVIII, Proceedings Of SPIE</i> 4345:273-284.					
	AN	HINSBERG et al. (2000), "Effect of Resist Components on Image Spreading During Postexposure Bake of Chemically Amplified Resists," <i>Advances in Resist Technology and Processing XVII, Proceedings of SPIE</i> 3999:148-160.					
	AO	HINSBERG et al. (2003), "Extendibility of Chemically Amplified Resists: Another Brick Wall?," <i>Advances in Resist Technology and Processing XX, Proceedings of SPIE</i> 5039:1-14.					
	AP	HOULE et al. (2000), "Determination of Coupled Acid Catalysis-Diffusion Processes in a Positive-Tone Chemically Amplified Photoresist," <i>J. Vac. Sci. Technol. B</i> 18(4):1874-1885.					
	AQ	KUNZ et al. (2001), "Experimental VUV Absorbance Study of Fluorine-Functionalized Polystyrenes," <i>Advances in Resist Technology and Processing XVIII, Proceedings of SPIE</i> 4345:285-295.					

Examiner Signature		Date Considered	6/20/06
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Substitute for form 1449A/PTO  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> (use as many sheets as necessary)			<b>Complete if Known</b>		
			Application Number	10/729,452	
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			Attorney Docket Number	ARC920030104US1	
Sheet	1	of	1		

U.S. PATENT DOCUMENTS							
Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
JSC	AR	4,356,296	10/26/82	Griffith et al.	526	242	
	AS	4,365,049	12/21/82	Tsunoda et al.	526	245	
	AT	4,452,998	6/5/84	Griffith et al.	560	221	
	AU	6,027,856	2/22/00	Nozaki et al.	430	281.1	
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	AW	6,106,998	8/22/00	Maeda et al.	430	280.1	
	AX	6,140,010	10/31/00	Iwasa et al.	430	270.1	
	AY	6,146,806	11/14/00	Maeda et al.	430	170	
	AZ	6,319,650	11/20/01	Gelorme et al.	430	270.1	
	BA	Serial No. 10/604,082		Filed 6/25/03	Hinsberg et al.		

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Jle	BB	JP 61281116 A	11/12/86	Japan			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
Jle	BC	ALLEN et al. (1997), "Deep-UV Resist Technology: The Evolution of Materials and Processes for 250-nm Lithography and Beyond," <i>Handbook of Microlithography, Micromachining, and Microfabrication Volume 1: Microlithography</i> , Chapter 4, pp. 321-375, P. Rai-Choudhury, Editor, SPIE Optical Engineering Press..	
	BD	FEDYNYSHYN et al. (2001), "High Resolution Fluorocarbon Based Resist for 157-nm Lithography," <i>Advances in Resist Technology And Processing XVIII, Proceedings of SPIE 4345:296-307</i> .	
	BE	KODAMA et al. (2002), "Synthesis of Novel Fluoropolymer for 157nm Photoresists by Cyclo-Polymerization," <i>Advances in Resist Technology and Processing XIX, Proceedings of SPIE 4690:76-83</i> .	
	BF	REICHMANIS et al. (1991), "Chemical Amplification Mechanisms for Microlithography," <i>Chem. Mater.</i> 3(3):394-407	
	BG	URRY et al. (1968), "Multiple Multicenter Reactions of Perfluoro Ketones with Olefins," <i>The Journal of Organic Chemistry</i> 33(6):2302-2310.	

Examiner Signature		Date Considered	6/2006
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.